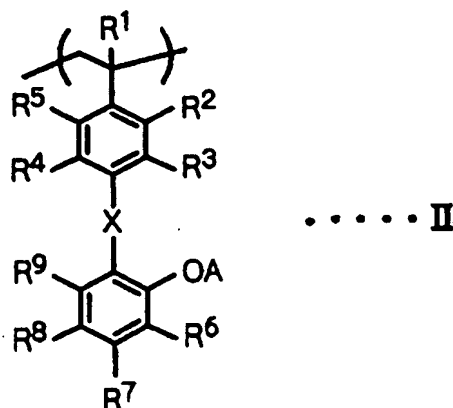


ABSTRACT

There is disclosed a photosensitive resin composition for interlayer insulating films, surface protection films or the like, which exhibits excellent resolution and can be developed with an aqueous alkaline solution. The

- 5 photosensitive resin composition is prepared using a polymer at least having a constitutional repeating unit represented by general formula II:



- wherein R^1 represents hydrogen atom or methyl group; R^2 to R^9 independently represent hydrogen atom, halogen atom or alkyl group having
 10 1 to 4 carbon atoms; X represents $-\text{CH}=\text{N}-$, $-\text{CONH}-$, $-(\text{CH}_2)_n-\text{CH}=\text{N}-$ or $-(\text{CH}_2)_n-\text{CONH}-$ and the N atom in X is bonded to a carbon atom in the benzene ring having AO- at an o-position; A represents hydrogen atom or a group being decomposed by an acid; and n represents a positive integer of 1 to 3.